

ABSTRACT OF THE DISCLOSURE

The invention includes a process which provides a projection system which projects an image of a predetermined pattern formed on a reticle to a photosensitive substrate; a setting process which sets a correction member which corrects residual aberration in the projection system at a predetermined position between a reticle setting position where the reticle is arranged and a substrate setting position where the photosensitive substrate is set; and a process which corrects degradation of optical characteristics of the projection system caused by setting the correction member at the predetermined position. Furthermore, the correction process includes a first adjusting process which adjusts at least one of the reticle setting position and the substrate setting position. Accordingly, even if a correction plate which corrects residual aberrations of the projection system is mounted into a projection optical path, deterioration of optical characteristics caused by mounting the correction plate is preferably corrected, and the invention makes it possible to manufacture an exposure apparatus equipped with a projection system adjusted in extremely high imaging quality.